

ELECTRONIC SUPPLEMENTARY INFORMATION

**Polymeric platform for the growth of chemically anchored ZnO nanostructures by ALD**

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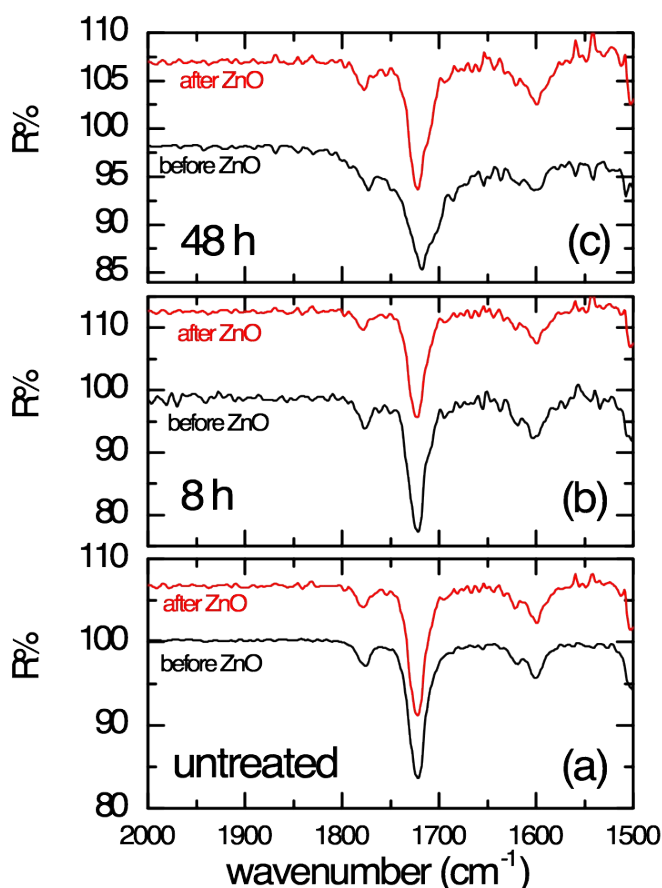


Fig E1: FTIR-ATR spectra related to (a) untreated, (b) 8h- and (c) 48h-treated ULTEM<sup>®</sup> 1000 films before (black line) and after (red line) ZnO ALD deposition.

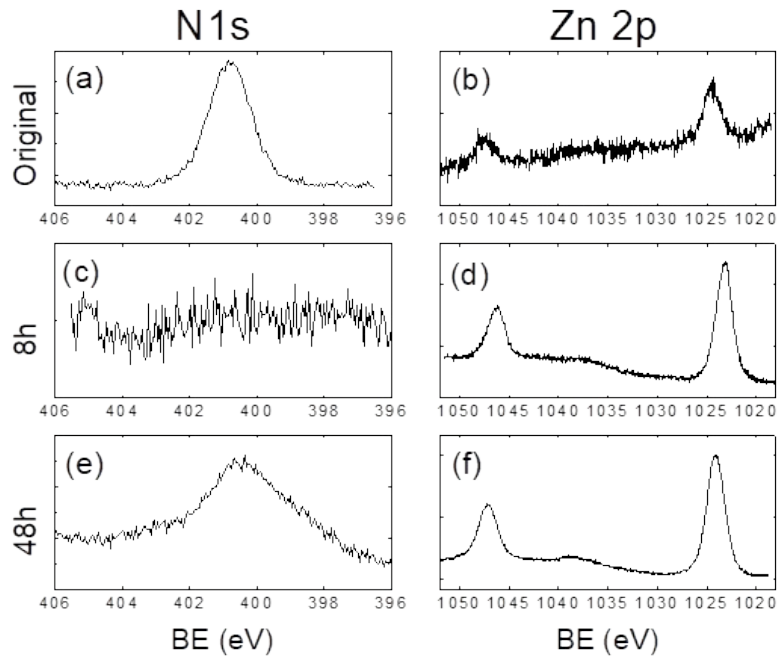


Fig E2: XPS spectra related to N1s and Zn 2p regions of (a) and (b) untreated; (c) and (d) 8h-; (e) and (f) 48h-treated ULTEM® 1000 films after ZnO ALD deposition.